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Application No.: 10/666,331 Preliminary Amendment

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Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims

(Original) In a plasma processing system, a method of removing a set of particles from a set of structures including yttrium oxide, comprising:

exposing said set of structures to a first solution including an oxidizer for a first period;

removing said set of structures from said first solution;

exposing said set of structures to a second solution including a keytone reagent for a second period;

removing said set of structures from said second solution; and mechanically rubbing a surface of said set of structures with a third solution including a first set of acids for a third period.

2. (Previously presented) The method of claim 1, further including the steps of: exposing said set of structures to a fourth solution including a second set of acids for a fourth period; and

exposing said set of structures to a fifth solution including a first set of alkalines for a fifth period.

- 3. (Currently amended) The method of claim 1, wherein said step of exposing said set of structures in to said first solution for a first period further includes mechanically rubbing said set of structures with an abrasive pad.
- 4. (Original) The method of claim 2, wherein said step of removing said set of structures from said first solution further includes rinsing said set of structures with de-ionized water.
- 5. (Original) The method of claim 4, further including drying said set of structures with a filtered inert gas.

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- 6. (Original) The method of claim 5, wherein said filtered inert gas comprises nitrogen.
- 7. (Withdrawn) The method of claim 2, wherein said step of exposing said set of structures to said second solution for a second period further includes cleaning said set of structures ultrasonically.
- 8. (Withdrawn) The method of claim 2, wherein after said step of exposing said set of structures in said second solution for a second period, said set of structures are rinsed and mechanically rubbed with an alcohol.
- 9. (Original) The method of claim 2, wherein said step of removing said set of structures from said second solution further includes rinsing said set of structures with de-ionized water.
- 10. (Original) The method of claim 9, further including drying said set of structures with a filtered inert gas.
- 11. (Original) The method of claim 10, wherein said filtered inert gas comprises nitrogen.
- 12. (Original) The method of claim 11, wherein said step of removing said set of structures from said third solution further includes rinsing said set of structures with de-ionized water.
- 13. (Original) The method of claim 12, further including drying said set of structures with a filtered inert gas.
- 14. (Original) The method of claim 13, wherein said filtered inert gas comprises nitrogen.

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- 15. (Original) The method of claim 2, wherein said step of removing said set of structures from said forth solution further includes rinsing said set of structures with de-ionized water.
- 16. (Original) The method of claim 15, further including drying said set of structures with a filtered inert gas.
- 17. (Original) The method of claim 16, wherein said filtered inert gas comprises nitrogen.
- 18. (Currently amended) The method of claim 44 15, wherein said step of removing said set of structures from said fifth solution further includes rinsing said set of structures with de-ionized water.
- 19. (Original) The method of claim 15, further including drying said set of structures with a filtered inert gas.
- 20. (Original) The method of claim 16, wherein said filtered inert gas comprises nitrogen.
- 21. (Withdrawn) The method of claim 2, wherein said oxidizer comprises H₂O₂.
- 22. (Withdrawn) The method of claim 2, wherein said second solution comprises H₂O₂.
- 23. (Withdrawn) The method of claim 22, wherein said H₂O₂ comprises from about 10% to about 30% of said second solution.
- 24. (Withdrawn) The method of claim 22, wherein said H₂O₂ comprises from about 20% to about 30% of said second solution.

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- 25. (Withdrawn) The method of claim 22, wherein said H_2O_2 comprises about 30% of said second solution.
- 26. (Original) The method of claim 2, wherein said first period comprises 30 minutes.
- 27. (Original) The method of claim 2, wherein said keytone reagent comprises acetone.
- 28. (Original) The method of claim 2, wherein said second period comprises 5 minutes.
- 29. (Withdrawn) The method of claim 2, wherein said third solution comprises H₂O₂.
- 30. (Withdrawn) The method of claim 2, wherein said first set of acids comprises HF.
- 31. (Withdrawn) The method of claim 30, wherein said HF comprises from about 2% to about 33% of said third solution.
- 32. (Withdrawn) The method of claim 30, wherein said HF comprises from about 2% to about 25% of said third solution.
- 33. (Withdrawn) The method of claim 30, wherein said HF comprises of about 2% of said third solution.
- 34. (Withdrawn) The method of claim 2, wherein said first set of acids comprises HNO₃.

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- 35. (Withdrawn) The method of claim 34, wherein said HNO3 comprises from about 2% to about 33% of said third solution.
- 36. (Withdrawn) The method of claim 34, wherein said HF HNO₃ comprises from about 2% to about 25% of said third solution.
- 37. (Withdrawn) The method of claim 34, wherein said HF HNO3 comprises of about 2% of said third solution.
- 38. (Original) The method of claim 2, wherein said third period comprises 1 minute.
- 39. (Previously Presented) The method of claim 2, wherein said fourth solution comprises H₂O.
- 40. (Original) The method of claim 2, wherein said second set of acids comprises CH₃COOH.
- 41. (Previously Presented) The method of claim 40, wherein said CH₃COOH comprises from about 2% to about 10% of said fourth solution.
- 42. (Previously Presented) The method of claim 40, wherein said CH₃COOH comprises from about 2% to about 6% of said fourth solution.
- 43. (Previously Presented) The method of claim 40, wherein said CH₃COOH comprises of about 4% to about 5% of said fourth solution.
- (Previously Presented) The method of claim 2, wherein said fourth period is 44. about 10 minutes.
- 45. (Withdrawn) The method of claim 2, wherein said fourth solution comprises H_2O_2

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- 46. (Original) The method of claim 2, wherein said first set of alkalines comprises NH₄OH.
- 47. (Original) The method of claim 46, wherein said NH₄OH comprises from about 8% to about 33% of said fifth solution.
- 48. (Original) The method of claim 46, wherein said NH₄OH comprises from about 6% to about 33% of said fifth solution.
- 49. (Original) The method of claim 46, wherein said NH₄OH comprises of about 25% of said fifth solution.
- 50. (Original) The method of claim 2, wherein said forth solution comprises H_2O_2
- 51. (Original) The method of claim 50, wherein said H₂O₂ comprises from about 8% to about 33% of said fifth solution.
- 52. (Original) The method of claim 50, wherein said H₂O₂ comprises from about 6% to about 33% of said fifth solution.
- 53. (Original) The method of claim 50, wherein said H₂O₂ comprises of about 25% of said fifth solution.
- 54. (Previously Presented) The method of claim 2, wherein said fifth period is about 10 minutes.
- 55. (Withdrawn) In a plasma processing system, a method of removing a set of particles from a set of structures including yttrium oxide, comprising:

exposing said set of structures to a first solution including a keytone reagent for a first period;

removing said set of structures from said first solution;

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exposing said set of structures to a second solution including an oxidizer for a second period;

removing said set of structures from said second solution; and mechanically rubbing a surface of said set of structures with a third solution including a first set of acids for a third period.

56. (Withdrawn) The method of claim 55, further including the steps of: exposing said set of structures to a fourth solution including a second set of acids for a fourth period; and

exposing said set of structures to a fifth solution including a first set of alkalines for a fifth period.

57. (Withdrawn) In a plasma processing system, a method of removing a set of particles from a set of structures including yttrium oxide, comprising:

exposing said set of structures to a first solution including an oxidizer for a first period;

exposing said set of structures to a second solution including a first set of alkalines with said oxidizer for a second period;

removing said set of structures from said second solution; and mechanically rubbing a surface of said set of structures with said third solution including a first set of acids for a third period.

58. (Withdrawn) The method of claim 57, further including the step of exposing said set of structures to a solution including a second set of acids for a fourth period.